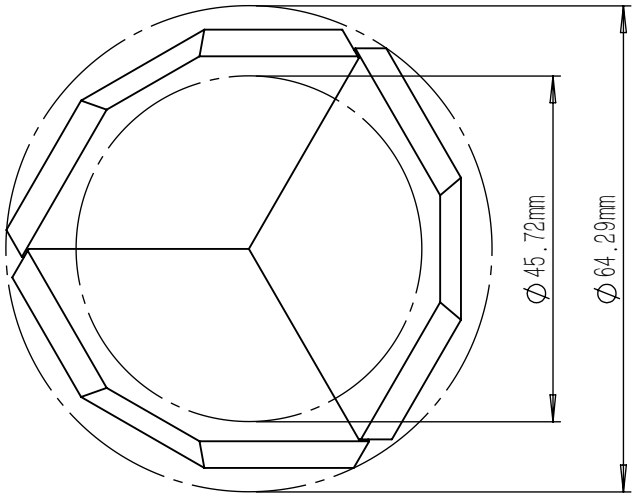
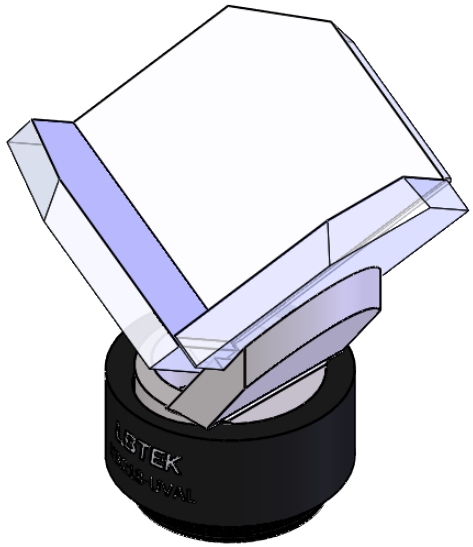
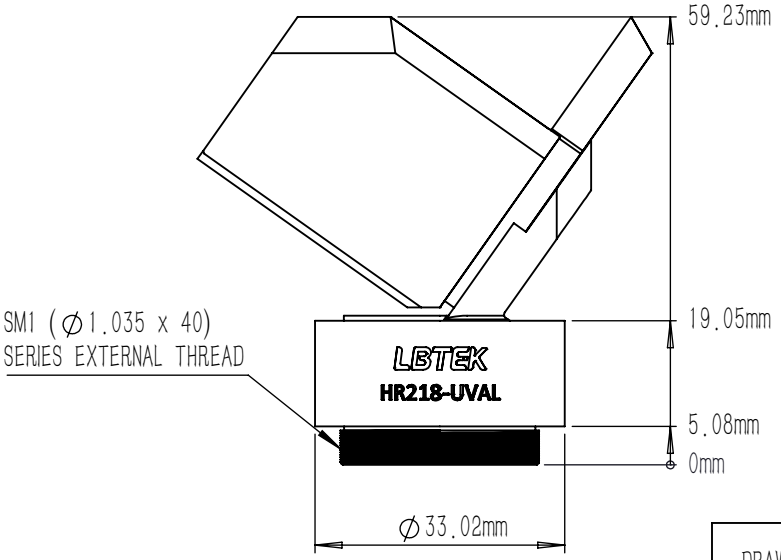
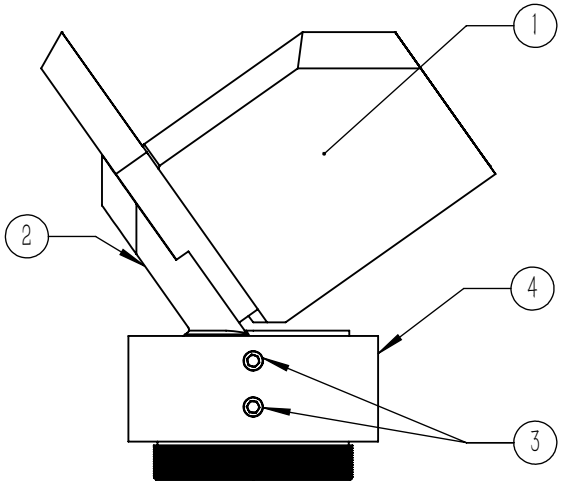
NO.	PART	MATERIAL
①	∅1.8″ HOLLOW RETROREFLECTOR MIRROR PROTECTED UV-ENHANCED ALUMINUM	UVFS
②	RETROREFLECTOR MOUNT	STAINLESS STEEL
③	M3 HEX SOCKET LOCKING SCREWS WITH NYLON HEADS x2	STAINLESS STEEL
④	1.0-INCH OPTICAL COMPONENT MOUNTING ADAPTER, WITH SM1 EXTERNAL THREADS, WITH ENGRAVING	ANODIZED ALUMINUM









NOTE:

1. OPERATION WAVELENGTH: 250 nm–600 nm
2. SUBSTRATE MATERIAL: UVFS
3. Substrate THICKNESS: 5 mm
4. CLEAR APERTURE: ∅45.72 mm (∅1.8″)
5. SURFACE QUALITY: 60/40
6. SURFACE FLATNESS: <2λ@633 nm
7. BEAM DEVIATION: <20 arcsec
8. COATING: PROTECTED UV-ENHANCED ALUMINUM
   Ravg>96.0%@250 nm–600 nm, 0° –45° AOI

DRAWING PROJECTION			LBTEK			
	NAME	DATE	HR218-UVAL			
DRAWN	LTAN	Apr./10th/26	HOLLOW RETROREFLECTOR MIRROR ∅1.8″, SM1, UVAL: 250 nm–600 nm			
APPROVAL	WCHEN	Apr./10th/26	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			N/A	110 g	1:1	A